





(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization International Bureau

(43) International Publication Date 21 December 2000 (21.12.2000)

PCT

(10) International Publication Number WO 00/77548 A1

(51) International Patent Classification7:

(21) International Application Number: PCT/GB00/02145

(22) International Filing Date:

2 June 2000 (02.06.2000)

(25) Filing Language:

English

G02B 6/132

(26) Publication Language:

English

(30) Priority Data:

GB 3 August 1999 (03.08.1999) GB

9913713.5 14 June 1999 (14.06.1999) 9918097.8

(71) Applicant (for all designated States except US): THE SECRETARY OF STATE FOR DEFENCE [GB/GB]; Defence Evaluation and Research Agency, A4 Building, Ively Road, Farnborough, Hampshire GU14 0LX (GB).

(72) Inventors; and

(75) Inventors/Applicants (for US only): MARTIN, Trevor [GB/GB]; DERA Malvern, St. Andrew Road, Malvern, Worcestershire WR14 3PS (GB). BALMER, Richard, Stuart [GB/GB]; DERA Malvern, St Andrew Road, Malvern, Worcestershire WR14 3PS (GB). AYLING, Stephen, Gerard [GB/GB]; DERA Malvern, St Andrew Road, Malvern, Worcestershire WR14 3PS (GB). MACLEAN, Jessica, Owens [GB/GB]; DERA Malvern, St Andrew Road, Malvern, Worcestershire WR14 3PS (GB). HEATON, John, Michael [GB/GB]; DERA Malvern, St. Andrews Road, Malvern, Worcestershire WR14 3PS (GB).

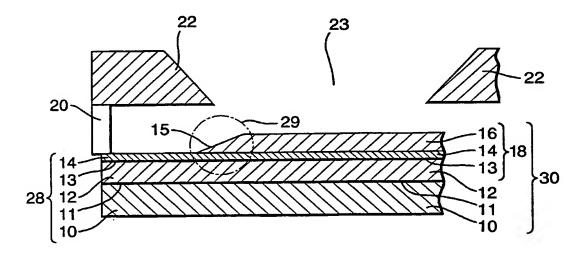
- (74) Agent: BOWDERY A.O.; D/IPR, DERA Formalities, A4 Bldg., Ively Road, Fanborough, Hampshire GU14 0LX
- (81) Designated States (national): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CR, CU, CZ, DE, DK, DM, DZ, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW.
- (84) Designated States (regional): ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG).

Published:

With international search report.

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

(54) Title: METHOD OF FABRICATING A SEMICONDUCTOR DEVICE



(57) Abstract: A method of fabricating a semiconductor device includes a step of growing at least one tapered epitaxial layer upon a supporting surface by chemical beam epitaxy, the plane of the taper being inclined to the supporting surface.

